



Sheet: 1 of: 1

FORM: PTO-1449 (REV: 7-80)	U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE 3 <sup>RD</sup>	Atty Docket No: 94-0280.04	Serial No: 09/470,650
INFORMATION DISCLOSURE STATEMENT BY APPLICANT		Applicant: Thomas A. Figura et al.	
(37 CFR 1.98(b)) (use several sheets if necessary)		Filing Date: 12/22/99	Group: 2813

## U.S. PATENT DOCUMENTS

Examiner Initial	Document Number	Date	Name	Class	Subclass
LAK	AA 6,117,764	09/12/00	Figura et al.	438	623
LAK	AB 5,950,092	09/07/99	Figura et al.	438	399
	AC				
	AD				
	AE				
	AF				
	AG				
	AH				
	AI				
	AJ				
	AK				
	AL				
	AM				

## FOREIGN PATENT DOCUMENTS

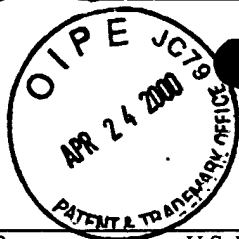
Examiner Initial	Document Number	Date	Country	Class	Subclass	Translation	
	AX					Yes	No
	AY					<input type="checkbox"/>	<input type="checkbox"/>

Initial

OTHER ART (including author, title, date, pertinent pages, etc.)

LAK	AZ	Application Serial No. 09/470,651, entitled USE OF A PLASMA SOURCE TO FORM A LAYER DURING THE FORMATION OF A SEMICONDUCTOR DEVICE, filed December 22, 1999; Thomas A. Figura, Kevin Donohoe, and Thomas Dunbar, inventors; attorney docket No. 94-0280.05; Preliminary Amendment filed December 22, 1999; Amendment After the Continued Prosecution Application and Response to the Office Action dated April 13, 2000 filed July 13, 2000; Response to the Office Action dated September 26, 2000 filed October 5, 2000; Amendment and Response to the Office Action Dated November 21, 2000 filed May 21, 2001.			
LAK	BA	Application Serial No. 09/471,460, entitled USE OF A PLASMA SOURCE TO FORM A LAYER DURING THE FORMATION OF A SEMICONDUCTOR DEVICE, filed December 22, 1999; Thomas A. Figura, Kevin G. Donohoe and Thomas Dunbar, inventors; attorney docket No. 94-0280.03; Preliminary Amendment filed December 22, 1999; Amendment After the Continued Prosecution Application and Response to the Office Action dated June 6, 2000; Amendment and Response to the Office Action dated November 21, 2000, filed May 21, 2001.			
Examiner:	Z. A. G.		Date Considered:	6/27/11	

EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication with applicant.



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<b>INFORMATION DISCLOSURE STATEMENT BY APPLICANT</b>  (37 CFR 1.98(b)) (use several sheets if necessary)		Applicant: <b>Thomas A. Figura et al.</b>	
		Filing Date: <b>12/22/99</b>	Group: <b>1765</b>

**U.S. PATENT DOCUMENTS**

Examiner Initial	Document Number	Date	Name	Class	Subclass	
ME	AA 5,904,799	05/18/99	Donohoe	156	345	
ME	AB 5,837,596	11/17/98	Figura et al.	438	446	
ME	AC 5,472,904	12/05/95	Figura et al.	437	67	
	AD					
	AE					
	AF					
	AG					
	AH					
	AI					
	AJ					
	AK					
	AL					
	AM					

**FOREIGN PATENT DOCUMENTS**

Examiner Initial	Document Number	Date	Country	Class	Subclass	Translation Yes	No
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	AY					<input type="checkbox"/>	<input type="checkbox"/>

Initial

**OTHER ART** (including author, title, date, pertinent pages, etc.)

	AZ		
	BA		
Examiner:	<i>[Signature]</i>		Date Considered: <i>8/2/11</i>

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INFORMATION DISCLOSURE STATEMENT BY APPLICANT  (37 CFR 1.98(b)) (use several sheets if necessary)		Applicant: Thomas A. Figura et al.	
		Filing Date: 12/22/99	Group:

## U.S. PATENT DOCUMENTS

Examiner Initial	Document Number	Date	Name	Class	Subclass	
LAK	AA 5,821,621	10/13/98	Jeng	257	759	
LAK	AB 5,804,259	09/08/98	Robles	427	577	
LAK	AC 5,496,773	03/05/96	Rhodes et al.	437	189	
LAK	AD 5,486,493	01/23/96	Jeng	437	195	
LAK	AE 5,476,817	12/19/95	Numata	437	195	
LAK	AF 5,443,941	08/22/95	Bariya et al.	430	313	
LAK	AG 5,422,310	06/06/95	Ito	437	192	
LAK	AH 5,422,294	06/06/95	Noble, Jr.	437	52	
LAK	AI 5,382,316	01/17/95	Hills et al.	156	643	
LAK	AJ 5,364,817	11/15/94	Lur et al.	437	192	
LAK	AK 5,364,809	11/15/94	Kwon et al.	437	52	
LAK	AL 5,354,715	10/11/94	Wang et al.	437	238	
LAK	AM 5,326,431	07/05/94	Kadomura	156	659.1	
LAK	AN 5,312,773	05/17/94	Nagashima	437	190	
LAK	AO 5,292,677	03/08/94	Dennison	437	52	
LAK	AP 5,286,675	02/15/94	Chen et al.	437	195	
LAK	AQ 5,284,787	02/08/94	Ahn	437	52	
LAK	AR 5,232,509	08/03/93	Min et al.	118	723	
LAK	AS 5,185,282	02/09/93	Lee et al.	437	47	
LAK	AT 5,162,248	11/10/92	Dennison et al.	437	52	
LAK	AU 5,150,276	09/22/92	Gonzalez et al.	361	313	
LAK	AV 5,110,712	05/05/92	Kessler et al.	430	312	
LAK	AW 5,096,849	03/17/92	Beilstein, Jr. et al.	437	67	
LAK	AX 5,084,413	01/28/92	Fujita et al.	437	189	
LAK	AY 5,066,607	11/19/91	Banerjee	437	52	
LAK	AZ 4,918,033	04/17/90	Bartha et al.	437	245	
LAK	BA 4,797,373	01/10/89	Malhi et al.	437	60	
LAK	BB 4,759,958	07/26/88	Numata et al.	427	255.6	

## FOREIGN PATENT DOCUMENTS

Examiner Initial	Document Number	Date	Country	Class	Subclass	Translation Yes	Translation No
	BC					<input type="checkbox"/>	<input type="checkbox"/>
	BD					<input type="checkbox"/>	<input type="checkbox"/>

Initial

OTHER ART (including author, title, date, pertinent pages, etc.)

LAK	BE	Tetsuo Ono, Ryoji Hamasaki and Tatsumi Mizutani, "Mechanism for CF Polymer Film Deposition through Deep SiO <sub>2</sub> Holes in Electron Cyclotron Resonance Plasma," Jpn. J. Appl. Phys. Vol. 35, pp. 2468-2471, Part 1, No. 4B, April 1996.
LAK	BF	Ephrath, L. M., "Teflon Polymer Mask For RIE of Contact Roles," IBM Technical Disclosure Bulletin, Vol. 25, No. 9, pp. 4587-4588, February 1983.
Examiner: <i>Z. Al</i>		Date Considered: <i>1/22/01</i>

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